	Hits	Search Text	DBs
71	9	((EUV or UV or VUV or DUV or X$2ray or ultraviolet) near22 (laser or ablat$4 or irradiat$4 or illuminat$4 or expos$4) near22 (resist or photoresist) near20 (pattern) near29 strip$4 near29 (remov$5)) and ((resist or photoresist) near12 (residu$3 or remain$4) near26 (UV or EUV or DUV or X$3ray or VUV or ultraviolet) near12 (irradait$4 or illuminat$4 or imping$4 or expos$4) near29 develop$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
72	9	((EUV or UV or VUV or DUV or X$2ray or ultraviolet) near22 (laser or ablat$4 or irradiat$4 or illuminat$4 or expos$4) near22 (resist or photoresist) near20 (pattern) near29 strip$4 near29 (remov$5)) and (((resist or photoresist) near12 (residu$3 or remain$4)) near26 (UV or EUV or DUV or X$3ray or VUV or ultraviolet) near22 (irradait$4 or illuminat$4 or imping$4 or expos$4) near29 develop$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
73	8	((EUV or UV or VUV or DUV or X$2ray or ultraviolet) near22 (laser or ablat$4 or irradiat$4 or illuminat$4 or expos$4) near22 (resist or photoresist) near20 (pattern) near29 strip$4 near29 (remov$5)) same (((resist or photoresist) near12 (residu$3 or remain$4)) near26 (UV or EUV or DUV or X$3ray or VUV or ultraviolet) near22 (irradait$4 or illuminat$4 or imping$4 or expos$4) near29 develop$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
74	2	((EUV or UV or VUV or DUV or X$2ray or ultraviolet) near22 (laser or ablat$4 or irradiat$4 or illuminat$4 or expos$4) near22 (resist or photoresist) near20 (pattern) near29 strip$4 near29 (remov$5)) and (((resist or photoresist) near12 (residu$3 or remain$4)) same (UV or EUV or DUV or X$3ray or VUV or ultraviolet) same (irradait$4 or illuminat$4 or imping$4 or expos$4) same develop$4) and (metal$3 near22 etch$4 near24 pattern)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB